

### **AMENDMENTS TO THE CLAIMS**

This listing of claims replaces all prior versions, and listing of claims in the application.

#### **Listing of the Claims:**

1. (Previously Presented) An apparatus for etching a glass substrate, comprising:  
an etching bath containing an etchant;  
a holder for supporting said glass substrate in the etching bath;  
an ultrasonic oscillator generating ultrasonic vibration on a surface of said substrate;  
wherein the ultrasonic oscillator is located in the interior of the etching bath; and  
an indicator displaying a temperature of the etching bath.
2. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said etchant comprises hydrofluoric acid.
3. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said holder comprises acid-resistant material.
4. (Original) The apparatus for etching a glass substrate of Claim 3, wherein said acid-resistant material comprises polytetrafluoroethylene.
5. (Original) The apparatus for etching a glass substrate of Claim 1, further comprising a thermometer for measuring the temperature of the etchant.
6. (Original) The apparatus for etching a glass substrate of Claim 1, further comprising a thermostat for signaling a specific temperature rise of said etchant.
7. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said holder supports a plurality of glass substrates.
8. (Cancelled)
9. (Cancelled)
10. (Original) The apparatus for etching a glass substrate of Claim 1, wherein said holder is located in an interior of said etching bath.

11. (Currently Amended) An apparatus for etching a glass substrate, comprising:  
an etching bath filled with an etchant;  
a holder for supporting said glass substrate in the etching bath;  
an ultrasonic oscillator generating ultrasonic vibration on a surface of said substrate, the ultrasonic oscillator is located in the interior of the etching bath; and  
an indicator [[for]] displaying a temperature of the etching bath.
12. (Previously Presented) The apparatus for etching a glass substrate of Claim 21, further comprising a control unit for receiving a temperature indicating signal from said temperature sensor and generating an etching termination signal when the temperature signal indicates an etching termination temperature.
13. (Original) The apparatus for etching a glass substrate of Claim 12, wherein said control unit determines said etching termination temperature from said temperature indicating signal.
14. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said etchant comprises hydrofluoric acid.
15. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said holder comprises acid-resistant material.
16. (Original) The apparatus for etching a glass substrate of Claim 15, wherein said acid-resistant material comprises polytetrafluoroethylene.
17. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said holder contains a plurality of glass substrates.
18. (Cancelled)
19. (Cancelled)
20. (Original) The apparatus for etching a glass substrate of Claim 11, wherein said holder is located in an interior of said etching bath.

21. (Previously Presented) The apparatus for etching a glass substrate of Claim 11, further comprising a temperature sensor installed in said etching bath, wherein the temperature sensor monitors the temperature of the etching bath.